

IN THE CLAIMS

The claim set is intended to reflect amendment of previously pending claims 11 and 33, and addition of new claim 42. The specific amendments to individual claims are detailed below.

Claims 1-10 (Previously cancelled)

11. (Currently amended) A system for making a thin-film device, the system comprising:

a first substrate-supply station that supplies a substrate having a major surface area, the substrate having a first layer, having a composition different than the substrate, formed on a first surface area of the substrate's ~~major surface area~~;

a first deposition station that deposits a second layer onto the first layer, wherein the first deposition station supplies an amount of ion-assist energy to the second layer to aid in crystalline layer formation while controlling a stoichiometry of the crystalline layer without substantially heating the substrate.

12. (Original) The system according to claim 11, wherein the first and second layers are part of a battery, the system further comprising:

a deposition station that deposits a photovoltaic cell on the battery.

13. (Original) The system according to claim 12, the system further comprising:

a station that attaches an integrated circuit to the substrate; and

a wiring station that forms conductive paths between the integrated circuit, the battery and the photovoltaic cell.

14. (Original) The system according to claim 11, the system further comprising:

a motion device that move the substrate, wherein the first and second layers are deposited on the substrate while the substrate moves in a continuous motion.

15. (Original) The system according to claim 11, wherein the substrate is a flexible material supplied from a roll, and the first and second layers are deposited on the substrate while the substrate moves in a continuous motion.

16. (Original) The system according to claim 11, wherein the first and second layer forms a cathode layer of a battery including the cathode layer; an anode layer, and an electrolyte layer located between and electrically isolating the anode layer from the cathode layer, wherein the anode or the cathode or both include an intercalation material.

17. (Original) The system according to claim 11, further comprising a deposition station that deposits an electrical circuit on the battery.

18. (Original) The system according to claim 11, wherein the substrate is a rigid material supplied from a cassette, and the first and second layers are deposited on the substrate while the substrate moves in a continuous motion.

19. (Original) The system according to claim 11, wherein the substrate is a polymer material having a melting point below about 700 degrees Celsius.

20. (Original) The system according to claim 11, wherein the energizing of the second layer includes supplying ions of at least 5eV.

21. (Original) A system for making a thin-film device, the system comprising:

a substrate-supply station that supplies a substrate having a major surface area, the substrate having a first layer on a first surface area of the substrate's major surface area;

means for depositing a second layer onto the first layer, wherein the means supplies energy to the second layer to aid in layer formation without substantially heating the substrate.

22 (Previously amended) A system for making a thin-film device, the system comprising:
a substrate-supply station that supplies a substrate having a major surface area;

a plurality of deposition stations that deposit layers onto the substrate including a first deposition station and a second deposition station, wherein the first and the second deposition stations each supply energy to the layer to aid in crystalline layer formation while controlling a stoichiometry of the respective crystalline layers without substantially heating the substrate.

23. (Previously amended) The system of claim 22 wherein the substrate-supply station supplies a continuous plastic sheet.

24. (Previously amended) The system of claim 22 wherein the substrate-supply station supplies a continuous set of wafers.

25. (Previously amended) The system of claim 22 wherein the plurality of deposition stations deposit a thin film battery.

26. (Previously amended) The system of claim 22 wherein the plurality of deposition stations deposits a capacitor.

27. (Previously amended) The system of claim 22 wherein the plurality of deposition stations deposits a thin film battery and a device powered by the thin film battery.

28. (Previously amended) The system of claim 22 wherein the plurality of deposition stations deposit a thin film battery and a device powered by the thin film battery, wherein the device is deposited onto the thin film battery.

29. (Previously amended) The system of claim 22 wherein the plurality of deposition stations deposit a thin film battery and a set of traces for electrically connecting a device to the thin film battery.

30. (Previously amended) The system of claim 29 further comprising a placement device for placing components onto the traces.

31. (Previously amended) The system of claim 22 wherein the at least one deposition station deposits an energy-conversion device.

32. (Previously added) The system of claim 11, wherein the second layer is a LiCoO_2 intercalation material, and the ion-assist includes ionized oxygen that combines with LiCo to form the LiCoO_2 intercalation material.

33. (Currently amended) The system according to claim 11, further comprising
a second substrate-supply station that supplies a the substrate before the first layer is deposited having a major surface area;
a second deposition station that deposits the first layer onto the substrate, wherein the second deposition station supplies ion-assist energy to the first layer to aid in crystalline layer formation while controlling a stoichiometry of the crystalline layer without substantially heating the substrate.

34. (Previously added) A system for making a thin-film device, the system comprising:
a first substrate-supply station that supplies a substrate having a major surface area, the substrate having a first layer, having a composition different than the substrate, formed on a first surface area of the substrate's major surface area;
a first deposition station that deposits a second layer onto the first layer, wherein the first deposition station supplies an amount of ion-assist energy to the second layer to aid in crystalline layer formation while controlling a stoichiometry of the crystalline layer without substantially heating the substrate, wherein the substrate is a flexible material supplied from a roll, and the first and second layers are deposited on the substrate while the substrate moves in a continuous motion, wherein the first and second layer forms a cathode layer of a battery including the cathode layer; an anode layer, and an electrolyte layer located between and electrically isolating

the anode layer from the cathode layer, wherein the anode or the cathode or both include an intercalation material.

35. (Previously added) The system according to claim 34, further comprising a second deposition station that deposits an electrical circuit layer on the battery.

36. (Previously added) The system according to claim 34, wherein the substrate is a polymer material having a melting point below about 700 degrees Celsius.

37. (Previously added) The system according to claim 34, wherein the energizing of the second layer includes supplying ions of at least 5eV.

38. (Previously added) The system according to claim 34, wherein the substrate is a polymer material having a melting point below about 700 degrees Celsius, and wherein the energizing of the second layer includes supplying ions of at least 5eV.

39. (Previously added) The system according to claim 21, wherein the substrate-supply station supplies a continuous plastic sheet.

40. (Previously added) The system according to claim 21, wherein the substrate-supply station supplies a sequential set of wafers.

41. (Previously added) The system according to claim 21, wherein the means deposit a thin film battery.

42. (New) The system according to claim 21, wherein the means for depositing the second layer includes means for aiding in crystal formation.
